

PATENT 2342-107P

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant:

Mitsuhiro HIRANO

Conf.:

3165

Appl. No.:

08/813,200,

Group:

2814

Filed:

March 7, 1997

Examiner:

M. DIETRICH

For:

SUBSTRATE PROCESSING APPARATUS WITH LOCAS

EXHAUST FOR REMOVING CONTAMINANTS (AS

AMENDED)

LARGE ENTITY TRANSMITTAL FORM

Assistant Commissioner for Patents Washington, DC 20231

May 28, 200

Sir:

Transmitted herewith is an amendment in the above-identified application.

The enclosed document is being transmitted via the Certificate of Mailing provisions of 37 C.F.R. § 1.8.

The enclosed document is being transmitted via facsimile.

The fee has been calculated as shown below:

	CLAIMS REMAINING AFTER AMENDMENT		HIGHEST NUMBER PREVIOUSLY PAID FOR		PRESENT EXTRA	RATE	ADDITIONAL FEE
TOTAL	4	-	26	=	0	\$ 18	\$0.00
INDEPENDENT	4	_	4	=	0	\$ 78	\$0.00
FIRST PRESENTATION OF A MULTIPLE CLAIM							\$0.00
						TOTAL	\$0.00

	Petition for(_) month(s) extends 1.136(a) is being filed, along with Notice of Appeal, concurrently	ith the ne	of time cessar	pursuant t y extensio	o 37 n fee	C.F.R s, tog	k. §§ 1.17 a ether with	and the						
\boxtimes	No fee is required.													
	A check in the amount of \$0.00 is enclosed.													
	Please charge Deposit A \$0.00. This form is submitted in	Account n triplicate		02-2448	in	the	amount	of						
If necessary, the Commissioner is hereby authorized in this, concurrent, and future replies, to charge payment or credit any overpayment to Deposit Account No. 02-2448 for any additional fees required under 37 C.F.R. §§1.16 or 1.17; particularly, extension of time fees.														
	Respectfully submitted,													
	BIRCH, STEWART, KOLASCH & BIRCH, LLP													
	By 43,102 for Michael K. Wiutter, #29,680													
MKM/F 2342-1	RLS/dsp 107P	P.O. Box Falls Chi (703) 20	urch, \	/A 22040-)	0747									

(Rev. 04/19/2000)

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PATENT 2342-0107P

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant:

Mitsuhiro HIRANO

Conf.:

3165

Appl. No.:

08/813,200

Group:

2814

Filed:

March 7, 1997

Examiner:

S. RAO

For:

SUBSTRATE PROCESSING APPARATUS WITH LOCAL

EXHAUST FOR REMOVING CONTAMINANTS (AS AMENDED)

AMENDMENT

Assistant Commissioner of Patents and Trademarks
Washington, D.C. 20231

May 22, 2001

Sir:

In reply to the Examiner's Office Action dated February 22, 2001, the following amendments and remarks are respectfully submitted in connection with the above-identified application.

IN THE CLAIMS:

Please amend the claims as follows:

10. (Four Times Amended) A substrate processing apparatus comprising.

a substrate processing chamber for processing a substrate;

a load lock chamber;

a gas supply for supplying gas into said load lock chamber;

a chamber exhaust for exhausting said load lock chamber, said chamber exhaust including an atmospheric pressure vent line and a vacuum exhaust line, said